

Transaction Information

Tool ID	GL04
Tool Status	Running Wafers
Location	East Fishkill, USA
Wafer Size	300 mm
Fab Section	Lithography
Tool Available Date	2022-08-15

General Product Information

Vendor Supplier	ASML
Model	XT1700Fi
Vintage	2007
Serial No	5633
Asset Description	ASML XT1700FI
Software Version	5.1
CIM	SECS GEM
Process	Immersion Lithography

Hardware Configuration (Fab)

System Type	Description	Quantity	Status
Main System	ASML 1700FI	1	OK
Handler System	NA		OK
Factory Interface	SMIF	1	OK
Options System		1	OK
Options System	Integrated Reticle library	1	OK
Options System	EFESE	1	OK
Options System	300mm Carrier handler	1	OK
Options System	AGILE	1	OK
Options System	DoseMapper	1	OK
Options System	Athena Narrow Marks	1	OK
Options System	DOE exchanger	1	OK
Options System			OK
Options System	SMASH Alignment	1	OK
Options System	BAseliner Focus	1	OK
Options System	Cymer Laser	1	OK
Options System		1	OK
Options System		1	OK
Options System	DOE exchanger	1	OK
Others			

Hardware Configuration (Subfab / Auxilliary Units)

Description	Quantity	Status
Main Body	1	OK

Missing/Faulty Parts / Accesories List

Description	Quantity
NONE	

Tool Pictures

General

tool pics



General

tool pics



General

tool pics



Manufacture Serial

SN plate



Additional Configuration Files

Software Key Overview

Machines are only shown if they

GL04

		XT1700i
Software Key	Software Key Value	5633
2 Sided IFM-beams for WS-X (expose)	Available for production	
	Not available	21-OCT-08
2 Sided IFM-beams for WS-X (measure)	Available for production	
	Not available	21-OCT-08
2D Barcode Reader	Absent	07-NOV-06
2D grid correction	Enabled	20-AUG-09
AA processing rack	MPCR processing rack	07-NOV-06
	MPCR2 processing rack	
ALE 1 Use	Calibration	07-NOV-06
AMCR configuration	No configuration specified	16-JUL-10
APACE used in production.	APACE is disabled in production.	16-JUL-10
AST offset usage during LOCO TIS	Disabled	23-MAR-15
Activate 2Dspg for long y-moves only. Protected	2Dspg for long y-moves only disabled	29-JUL-14
Activate ESO MAX speed Allowed. Protected	ESO MAX Speed Allowed Disabled	29-JUL-14
Activate Edge Speed Limiter. Protected	Edge Speed Limiter Disabled	16-JUL-10
	Edge Speed Limiter Standard	
Activation of the airknife during hovering	Airknife disabled during hovering in wet mode	
	Airknife enabled during hovering in wet mode	16-JUL-10
Active Pupil Aberration Correction Element type	APACE Absent	18-DEC-09
Active Pupil Aberration Correction lens Element	Metrology does not use any APACE	16-JUL-10
Active wafer release for dry WS	False	21-OCT-08
Adjust LHV oscillation threshold of the green laser	Enable decreased green laser oscillation threshold	20-JUL-12
Air Gauge	Present	20-AUG-09
Air Gauge Improved Levelling	AGILE1	29-JUL-14
Alignment Camera Mirror	Absent	07-NOV-06
Alignment Sensor Type	Athena Narrow Marks OM	07-NOV-06

	Smash OM	
Alignment Settle Time	Basic	23-MAR-15
Alignment laser configuration	2 color laser	17-JUL-07
	4 color laser	
Allow L1L7 Type 1 Optimization	Absent	07-NOV-06
	Present	
Allow different Exp,TIS Align set	Absent	21-OCT-08
Allow even orders usage	Absent	07-NOV-06
	Present	
Allow wafer plane deviation check with Focus Monitoring	Disabled	31-JAN-09
	Enabled	
Angular sensitivity corrections of Spot Sensor on Chuck 1	Disabled	16-JUL-10
	Enabled	
Angular sensitivity corrections of Spot Sensor on Chuck 2	Disabled	16-JUL-10
	Enabled	
Application Specific Lens Heating Calibration & Verification	Present	16-JUL-10
Application Type	Scanner Application	07-NOV-06
Apply clamping grid correction during wafer align	disabled;	16-JUL-10
	enabled;	
Assure System Snapshots	Assure System Snapshots not allowed	29-JUL-14
Ast offset correction in TIS LHFB/LOCO (Version 3)	Disabled	21-OCT-08
Athena Focus Improvements 1	Present	07-NOV-06
Athena Narrow Marks Twinscan	Present	07-NOV-06
Attenuator Mirror Type	Quartz Attenuator Mirror	16-JUL-10
Attenuator Type	Variable	07-NOV-06
Automated DOE Exchanger	Present	07-NOV-06
Automated DOE Exchanger Architecture	16 slots	07-NOV-06
Automated Lens Heating Calibration	Disabled	
	Enabled	16-JUL-10
Automated Reticle Transport System	Present	22-JAN-07
Automatic CUA	Absent	07-NOV-06

Automatic CUA exchanger architecture	Adjacent to the Rema objective	07-NOV-06
Automatic PCE exchanger	Present	07-NOV-06
Availability of WID readout functionality	WID readout functionality absent	19-MAR-19
Availability of chucks in the waferstage compartment.	Both chucks are present.	16-JUL-10
Availability of inline WTQT functionality	Inline WTQT functionality disabled	19-MAR-19
Availability of the FlexWave module	FlexWave module not available	29-JUL-14
Avoid I1 or I2 mark on TIS plates	Disabled;	16-JUL-10
Avoid Track INPUT/OUTPUT conflicts, Raise AS after APR	Avoid Track INPUT/OUTPUT conflicts disabled	21-OCT-08
	Avoid Track INPUT/OUTPUT conflicts enabled	
BA-XY Reticle preference: V1 or V2; default is V2	V1 BA-XY Reticle	23-MAR-15
BALE Type	Piezo Valves	
	WS15G Valves	21-OCT-08
Barcode Reader configuration at IRL.	Not configured. Update according to the BCR present at IRL.	12-APR-21
BaseLiner Optima WEC/REC Control	BaseLiner Optima WEC/REC application is disabled.	29-JUL-14
BaseLiner focus control.	BaseLiner-Focus application is enabled.	23-JUL-10
BaseLiner focus high order intrafield	BaseLiner-Focus high order intrafield is disabled.	16-JUL-10
BaseLiner overlay control.	BaseLiner-Overlay application is enabled.	23-JUL-10
Baseliner diffraction based focus stability control	Baseliner diffraction based focus stability control disabled	29-JUL-14
Beam Control	Closed loop	07-NOV-06
Beam Shaping Module	No Beam Shaping Module present	12-APR-21
Behavior of the FlexWave module	FlexWave not controllable	29-JUL-14
Bubble Extraction Seal Setting	Bes boost 2	16-JUL-10
CDC	Enabled	07-NOV-06
CT Miscellaneous Rack	Present	07-NOV-06
Capacitive z-height sensor type.	Extended Z sensor board	07-NOV-06
Carrier Handler Type	Mark II 300 Foup	07-NOV-06
	Mark III 300	
Center pole location in the machine	Center pole is located in the center	16-JUL-10
	Center pole is shifted towards the measure area	
Changed Short Stroke diff XY controller	Disabled	07-NOV-06
Choice of COWA1 vertical setpoint calculation	Wait for current wafer capture result for the calculation	07-AUG-17

Choice of avoidance routing.	Phase 2	07-NOV-06
Choice of horizontal stage align setpoint	Wait for vertical stage align result	29-JUL-14
Choice of wafer capture position	Perform wafer capture at SOSI scan-in position	07-AUG-17
Chuck 1 wafer size	300mm	07-NOV-06
Chuck 2 wafer size	300mm	07-NOV-06
Chuck Dedication	Enhanced	22-NOV-07
Circuit Dependent FEC	Present	07-NOV-06
Clean Air Configuration	Air Shower Type 7A low pressure	07-NOV-06
	Others	
Clean Air Temperature Control	Driver and ACC	07-NOV-06
Clean Air Temperature Performance level	Level 2	21-OCT-08
Closing disk type	SiC closing present	22-NOV-06
CoWa2 vertical setpoint	Use Global Wafer Wedge result as CoWa2 vertical setpoint	23-MAR-15
Combined stage alignment	Disabled	16-JUL-10
	Enabled	
Communication with Air Control Cabinet	RS232 communication	16-JUL-10
Computational ASCAL	Commercial cASCAL option disabled	29-JUL-14
Configuration Identification CARM Stages Stack	No Configuration Specified.	29-JUL-14
Configuration id for reticle handling electronics	No configuration specified	29-JUL-14
Configuration identification for AMCR electronics	No configuration specified	29-JUL-14
Configuration identification for PCHR (Handlers) electronics	No configuration specified	29-JUL-14
Configuration identification for PCSR electronics	No configuration specified	29-JUL-14
Configuration identification for projection mechatronics	No Configuration Specified.	29-JUL-14
Configuration identification for projection software	No Configuration Specified.	29-JUL-14
Configuration identification of the accelerometers	Accelerometer configuration 1	29-JUL-14
Configuration identification reticle positioning electronics	No configuration specified	29-JUL-14
Configuration identification wafer positioning electronics	No configuration specified	29-JUL-14
Configuration identifier planar stage chuck 1 linear axis	No configuration specified	29-JUL-14
Configuration identifier planar stage chuck 1 long stroke	No configuration specified	29-JUL-14
Configuration identifier planar stage chuck 1 short stroke	No configuration specified	29-JUL-14
Configuration identifier planar stage chuck 2 linear axis	No configuration specified	29-JUL-14

Configuration identifier planar stage chuck 2 long stroke	No configuration specified	29-JUL-14
Configuration identifier planar stage chuck 2 short stroke	No configuration specified	29-JUL-14
Configuration of planar stage chuck 1 corner-cubes	No configuration specified	29-JUL-14
Configuration of planar stage chuck 2 corner-cubes	No configuration specified	29-JUL-14
Configuration of the In-Vacuum Robot Z-axis motor.	No configuration specified	29-JUL-14
Constrained fit	Disabled	21-OCT-08
Continuous clampable wafer table for dry WS	Absent	21-OCT-08
Control the APCAP miscapture recovery	The APCAP miscapture recovery is disabled	16-MAY-16
Controls parasitic stiffness type	Type 1, no spec selection	16-MAY-16
Corr. Per Exposure Lot reporting includes ADELSbcoverlay.	Include the ADELSbcoverlay intrafield contribution.	23-MAR-15
DOEs in lower disk ADE	Not Applicable	28-MAR-17
DOSEMAPPER	Present	07-NOV-06
DOSE_MAPPER_1	Present	07-NOV-06
DUV Lightsource Power Level	60.00 Watt	07-NOV-06
Data collection not covered by FOCUS and OVERLAY	Disabled	06-NOV-11
Dedicated Stage Alignment	Disabled	29-JUL-14
Delay ret move from RS during idle cond, m-act and CPDs	Delay reticle move requests from or to stage	29-JUL-14
Depolarizer type	no retarder but pce-depolarizer	16-JUL-10
Depth of Focus enhancement with adjustable laser bandwidth	Laser bandwidth is not adjustable	16-JUL-10
Derived Lens Type for common metrology software	07	29-JUL-14
	91	
Describes at what plane the BMU measures	Correct for BMU below DOE1 level	16-JUL-10
Determination of NA ellipticity	Disabled	21-OCT-08
Diaphragm Limiter	Absent	07-NOV-06
Diff pressure correction for IFM beams	Absent	21-OCT-08
	Present	
Disable or enable the encryption of Recipes send to the Tool	Do not encrypt any recipes or layer files on Tool.	16-MAY-16
Docking wheels at WH unload	Absent	07-NOV-06
Dose Intensity Optimization	Disable Dose Intensity Optimization;	03-SEP-10
Dose System Performance Test for Lithoguide	Present	07-NOV-06
Dose evaluation functionality for UV systems	Dose Evaluation for UV systems disabled	28-MAR-17

DoseSystemPerformanceTest sequence	Test sequence 1	16-JUL-10
Dosecontrol Hardware	DCB	07-NOV-06
Double TIS scan	Disabled	21-OCT-08
Dynamic Performance Calculation	Mark 2	07-NOV-06
E-chuck Flatness Qualification Test	Disabled	07-NOV-06
EDA Interface	Disabled	21-OCT-08
EDA Interface standard Freeze	Level I	12-APR-21
EDO	Disabled	16-JUL-10
EFESE	Absent	
	Present	23-JUL-10
ESC wait and repeat functionality	ESC wait and repeat functionality is not available	28-MAR-17
ESO Manual Override	ESO Manual Override Disabled	06-NOV-11
EUV Lightsource Architecture	Laser Produced Plasma	29-JUL-14
EUV sources	Pilot and following Source(s)	29-JUL-14
Editable M-action queues	Editable M-action queues disabled	16-JUL-10
Electronics-box version of chuck 1	No version specified	29-JUL-14
Electronics-box version of chuck 2	No version specified	29-JUL-14
Enable ExpoFlex functionality	ExpoFlex is unavailable	29-JUL-14
Enable or disable SLIP / Intensity protection	SLIP / Intensity protection is disabled	03-NOV-15
Enable or disable image alignment fading correction	Disable image alignment fading correction	03-NOV-15
Enable the Maintenance Assistant	Disable Maintenance Assistant	07-NOV-06
	Enable Maintenance Assistant	
Enable the new fit algorithm, supporting BGRM for periodic scan types, when enabling this switch.	Disable the SMASH FFT fit algorithm for periodic scan types.	29-JUL-14
Enable to support SMASH XY mark types.	SMASH XY marks are not supported.	16-JUL-10
Enable/Disable LoS2SS error FF on measure side	LoS2SS error FF settings according to MCs	29-JUL-14
Enables RA Multiple Scans	Disable RA Multiple Scans	29-JUL-14
Enables SA Multiple Scans	Disable SA Multiple Scans	29-JUL-14
Enables idle condition chuck swap	Wafer Stage Idle conditioning for immersion disabled	28-MAR-17
Enables system idle conditioning	System idle conditioning disabled	29-JUL-14
Energy Sensor	Star TechC	07-NOV-06

Energy sensor calibration type. Protected	Normal	29-JUL-14
Enhanced Exposure Overlay	Full	07-NOV-06
Enhanced Throughput Reticle Alignment	Extended	07-NOV-06
Enhanced exposures 1	Present	07-NOV-06
Enhancements in Reticle Monitor	no enhancements	21-OCT-08
Equipment Constants via SECS interface	Disabled	07-NOV-06
	Enabled	
Exchangeable Last Lens Element	Present	07-NOV-06
Exchangeable Pupil Lens Element	EPL Type INACTIVE	15-FEB-12
Exposure routing throughput optimization for KrF	Exposure routing throughput optimization for KrF is disabled	23-MAR-15
Extend IRIS maximum particles scanned to 50000.	Absent	11-SEP-07
	Present	
Extended LS areas	Enabled	16-NOV-06
Extended Lens Heating History (ELHH)	Enabled	16-JUL-10
Extended Spot Sensor Matching	Present	07-NOV-06
Extended Zone Alignment	Disabled	29-JUL-14
Extended maximum for FILS Timeout.	Standard	10-NOV-10
Extended measurements after expose	Disabled	16-JUL-10
Extended minimum for FILS Timeout.	Standard	10-NOV-10
Extreme Clean Humidified Air	Present	07-NOV-06
FOCAL Measurement for Lithoguide	Present	07-NOV-06
FSM Flexibility package	Disabled	21-OCT-08
Fast Avoidance Routing	Disabled	29-JUL-14
Fast VSA	Fast VSA is disabled	23-MAR-15
Fast Wobble	Disabled	
	Enabled	29-JUL-14
Field Dependent DOE Exclusion library	present	19-MAR-19
Field width optimised leveling	Disabled	21-OCT-08
Filtering of the SUSD correction.	Filtered SUSD correction is disabled.	29-JUL-14
FlexRay Control Rack Configuration	Absent	16-JUL-10
FlexWave Mode for Production	NONE - FlexWave is not used for production	29-JUL-14

Flexible Productivity	Enhanced productivity mode disabled	03-NOV-15
Flexray illuminator	Flexray Absent	16-JUL-10
Focus Data Collection	Absent	07-NOV-06
Focus Improvement Package (OBSOLETE key).	OBSOLETE.	29-JUL-14
Focus Monitoring	Absent	22-JAN-07
	Present	
Functional use of Active Elements	BALE function as BALE	21-OCT-08
Gas Control Unit Type	Ultra High Flow (UHF)	07-NOV-06
Gas Facilities: Gas Supply Lens Manipulator	Gas supply lens manipulator hardware not present	29-JUL-14
Gas Facility / Airknife: Point Of Use Humidifier	No point of use humidifier hardware present.	29-JUL-14
Gridmapper	Enabled	20-AUG-09
Hardware configuration identification of wafer clamps	CF unit	29-JUL-14
Hardware configuration identification of wafer table clamp	CFC unit	29-JUL-14
Hardware configuration of LoS2BM actuator version	No configuration specified	29-JUL-14
High resolution System performance	Disabled	28-MAR-17
IFM Laser Configuration	AOM Recombo Laser	07-NOV-06
ILIAS Fast Zernike concatenation	ILIAS Fast Zernike concatenation disabled	29-JUL-14
ILIAS Functionality For Lithoguide	Present	07-NOV-06
ILIAS Pupil measurement performance node	ILIAS Pupil measurement performance node 17	29-JUL-14
	ILIAS Pupil measurement performance node 19	
ILIAS Sensor Location	Both	07-NOV-06
ILIAS Zernike measurement performance node	ILIAS Zernike measurement performance node 17	29-JUL-14
	ILIAS Zernike measurement performance node 19	
ILIAS lens setup	Absent	07-NOV-06
ILIAS number of supported Zernikes	ILIAS number of supported Zernikes 37	29-JUL-14
ILIAS sensor type chuck 1	Hyper NA MK3	07-NOV-06
	Hyper NA MK5	
ILIAS sensor type chuck 2	Hyper NA MK3	07-NOV-06
	Hyper NA MK5	
IRL barcode reader type	1D barcode reader is present at IRL	12-APR-21
ISIS Functionality For Lithoguide	Absent	07-NOV-06

Identification of ESC hardware variants Chuck1	No clamp hardware available	29-JUL-14
Identification of ESC hardware variants Chuck2	No clamp hardware available	29-JUL-14
Identification of Positioning Module Supply Box version	No configuration specified	29-JUL-14
Identification of SLR brakebox type	Type 1 brakebox hardware	29-JUL-14
Identification of SLR clamp voltage	No voltage used on SLR clamps	29-JUL-14
Identification of SUR brakebox type	Type 1 brakebox hardware	29-JUL-14
Identification of SUR clamp voltage	No voltage used on SUR clamps	29-JUL-14
Identification of VPA clamp voltage	No voltage used on VPA clamps	29-JUL-14
Ifm config at measure side.	8 axes	07-NOV-06
Illumination modes	All illumination modes	07-NOV-06
Illuminator Machine Safety Hardware	PTI board	16-JUL-10
Illuminator Type	170	07-NOV-06
	190	
Illuminator platform	Aerial XP	07-NOV-06
Illuminator temperature sensors	No temperature sensors present	29-JUL-14
Image quality data path arch	Data path architecture A	16-JUL-10
Imaging Control Rack Configuration	IMCR	07-NOV-06
Imaging Electronics Architecture	B Architecture	07-NOV-06
Imaging Fading Control	Lens set-up only	21-OCT-08
Imaging Generic Power Amplifier	Ten Axis Power Amplifier	07-NOV-06
Imaging performance package	Standard imaging performance settings for non-8xy	06-NOV-10
Immersion	Present	07-NOV-06
Immersion Hood Sub version	Sub-Version 1	20-AUG-09
Immersion Hood SubSub version	Not Applicable	29-JUL-14
Immersion Hood version	Version 4	20-AUG-09
	Version 5	
Immersion hood heater configuration	Four segmented heaters on top	
	Internal single segmented heater	16-JUL-10
Immersion style Final XY tools for Dry Systems	Disabled	29-JUL-14
Improved CDFEC/FWOL application on non-yielding fields.	Enabled	29-JUL-14
Improved Contrast Control	Absent	

	Present	20-AUG-09
Improved Edge Field Leveling	Disabled	
	Enabled	29-MAR-17
Improved FSM algorithm. Part of FIP-1 commercial package.	Disabled	29-JUL-14
Improved Maintenance action scheduling.	Disabled	07-NOV-06
Improved Reticle Control	Basic TOP-RC behavior	04-OCT-18
Improved robustness DPCM fit	Enable improved robustness DPCM fit	29-JUL-14
Improved wafer reject mode	Disabled	21-OCT-08
	Enabled	
Improvements for reticle handling	Disabled	21-OCT-08
In situ Wafer Table Stone Cleaning	Absent	07-NOV-06
	Present	
In situ Wafer Table Stone Cleaning Hardware Version	Stone 1	29-JUL-14
	Stone 2	
Indicate which leveling spec shall be used.	The leveling spec is unknown.	16-MAY-16
Indicates the method used to detect a wafer on VPA	Detect wafer using the Vacuum Prealigner electrostat. clamps	29-JUL-14
Indicates whether the SFPM model is enabled	The SFPM model is disabled	29-JUL-14
Indicates which overlay spec is used	The overlay spec is set to SPEC_1	25-MAY-18
Indication what kind of AM controller hardware is present	DICR	
	SUCR	07-NOV-06
Inlet restriction for clean air	Inlet restriction at right side	07-NOV-06
Insert a delay time before starting a Lot (lens heating).	Disabled	16-JUL-10
Integrated Reticle Inspection System	PPD1 with IRIS1 functionality.	11-SEP-07
	PPD2 with IRIS5um functionality.	
Integrated Reticle Inspection System Configuration.	Disable creation of OSIRIS viewable files.	11-SEP-07
	Enable creation of OSIRIS viewable files for PPD2 systems.	
Integrated Reticle Library	IRL with original functionality	20-AUG-09
Intensity Calibration Per DOE	Disabled	21-OCT-08
	Enabled	
Intensity Calibration Type	Type 1	12-APR-21
Interferometer Electronics	lfsr	07-NOV-06

Interferometer axis version at exposure	3 plus 1 axis	07-NOV-06
Interfield Scan Up Scan Down focus correction	SUSD enabled model type 1	
	SUSD enabled model type 2	17-NOV-08
Intrafield Higher Order Process Corrections	Disabled	
	Enabled	23-JUL-10
Intrafield Higher Order Process Corrections Per Exposure	Intrafield HOPC per exposure is Disabled	29-JUL-14
Intrafield Wafer Alignment	Disabled	21-OCT-08
Iris feature Scan	Absent	07-NOV-06
	Present	
Is NA accuracy measurement allowed?	Disabled	21-OCT-08
Is the UPS Ethernet connected to the Twinscan.	UPS is not connected to the Twinscan.	29-JUL-14
Is this a machine with a safety PLC.	Safety PLC is not available in the Twinscan.	29-JUL-14
LAR event log pollution reduction	Enable LAR event log pollution reduction	29-JUL-14
LCI WaitWatcher plug-in	Absent	07-NOV-06
LCW Circuit set-up	Pressure Version 1	07-NOV-06
LEC Rack in Electronic Architecture	Absent	07-NOV-06
LS focus node	LS focus node 5	07-NOV-06
LS spot coverage	Absent	07-NOV-06
LS_CPU_CONFIG	1 CPU available	
	2 CPU's available	07-NOV-06
LS_PEMM_CONFIG	Absent	
	Present	07-NOV-06
LVT modeling version.	LVT model version 1 is enabled.	29-JUL-14
Laminar Bottom Hood	Absent	07-NOV-06
Large Range Leveling	Disabled	03-NOV-15
Laser Gas Life eXtension	Disable Laser Gas Life eXtension;	21-OCT-08
Laser capability for retrieving High Bandwidth Data	Laser does not provide Bandwidth Data	29-JUL-14
Layout Usage TIS Sensor	DUV TIS Sensor	29-JUL-14
Layout Version Number TIS Fiducial	TIS Fiducial Layout Version 1	29-JUL-14
Layout Version Number TIS Plate 1 on Chuck 1	TIS Plate 1 Layout Version 5	07-NOV-06
	TIS Plate 1 Layout Version 5.5	

Layout Version Number TIS Plate 1 on Chuck 2	TIS Plate 1 Layout Version 5	07-NOV-06
	TIS Plate 1 Layout Version 5.5	
Layout Version Number TIS Plate 2 on Chuck 1	TIS Plate 2 Layout Version 5	07-NOV-06
	TIS Plate 2 Layout Version 5.5	
Layout Version Number TIS Plate 2 on Chuck 2	TIS Plate 2 Layout Version 5	07-NOV-06
	TIS Plate 2 Layout Version 5.5	
Layout dependent corrections.	Layout dependent effects are not corrected.	19-MAR-19
Lens Active Vibration Absorber	Absent	29-JUL-14
Lens Circuit Water Flow	High Immersion	07-NOV-06
Lens Heating Feedback	Absent	07-NOV-06
Lens OverPressure Compensation	OverPressure Compensation Disabled	06-NOV-10
Lens Top Tool Connection	Lens Top Tool can not be mounted on top of the Lens	07-NOV-06
Lens Type	07	07-NOV-06
	91	
Level Sensor Processing Rack	MPCR	07-NOV-06
Leveling Verification Test for Lithoguide	Present	07-NOV-06
Levelling throughput improvement on measure side	Levelling throughput package A	
	No levelling throughput package	21-OCT-08
Light source selection, for FIR laser	Light source selection undefined	25-MAY-18
Light source selection, for NIR laser	Light source selection undefined	25-MAY-18
Light source selection, for green laser	Light source selection undefined	25-MAY-18
Light source selection, for red laser	Light source selection undefined	25-MAY-18
Light-source Architecture	Laser	07-NOV-06
Light-source Type	Cymer Laser: XLA 360 60W, 10 mJ, 6.0kHz	07-NOV-06
	GPI Laser: GT61A4 60W, 10 mJ, 6.0kHz	
Light-source Wave-length	193nm	07-NOV-06
Liquid Particle Counter Unit	No Liquid Particle Counter Unit installed	21-OCT-08
Lithoguide Imaging Recipes	Absent	07-NOV-06
	Present	
LoCo C2C drift correction	Disabled	28-MAR-17
Load Robot Internal Docking	WH LR Without Damping	16-JUL-10

Load Robot Wrist Assy Type	WH LR Wrist Long Tension Rod	16-JUL-10
Loadport barcode reader type	Original barcode reader at the loadports	29-JUL-14
Location of PARIS sensor on chuck 1	No PARIS sensor on chuck 1	29-JUL-14
Location of PARIS sensor on chuck 2	No PARIS sensor on chuck 2	29-JUL-14
Log missed translations	Disabled	07-NOV-06
Long Stroke Sliding Mode Controller	Disabled	29-JUL-14
Lot Alignment Report Encryption	Unencrypted	07-NOV-06
Lot Correction Sequence	Type D	07-NOV-06
	Type E	
Lot Overhead Reduction	LOR2	07-NOV-06
Lot Report Data Category	Enhanced Diagnostics	07-NOV-06
MALE used in production.	MALE is disabled in production.	16-JUL-10
MDL Viewer	Site View	07-NOV-06
Machine Architecture	XT Machine Architecture	07-NOV-06
Machine Location	Customer Site	22-JAN-07
Machine Performance level	None	03-NOV-15
Machine Specification	F Specification	07-NOV-06
	G Specification	
Machine Type	1700	07-NOV-06
	1900	
Max alignment speed	Setting 2	07-NOV-06
Maximum Reticle ID Length	24 Characters	16-NOV-06
Maximum numerical aperture (NA) allowed in Lot Production	level 0	29-JUL-14
Measure and model strategy for vertical stage align	VSA and advanced XVSA	16-JUL-10
	iVSA	
Method for alignment of the laser beam	Align beam by optimizing pupil telecentricity params: LUBB	16-JUL-10
Metroframe Circuit Water Cabinet	Absent	07-NOV-06
Metroframe Temperature Performance level	Level 1	16-JUL-10
Metroframe type	TYPE_A	07-NOV-06
Metrology overlay setup method	Metrology overlay setup calibration to nominal	23-MAR-15
Modelling for MAXYS	Absent	07-NOV-06

Motor Circuit Water Flow	High Immersion	07-NOV-06
Move profile parameter configuration chuck 1	Not specified	29-JUL-14
Move profile parameter configuration chuck 2	Not specified	29-JUL-14
Multi Functional Exchangeable Lens Element	Projection lens has no MF-EPLE	16-JUL-10
Multifunction Active Lens Element	0	21-OCT-08
Multifunctional Active Elements	0	21-OCT-08
Multilingual UI	Absent	07-NOV-06
Multiple wafers on output path configuration	Only one wafer at a time on the output path possible	28-MAR-17
NA Control Architecture	NA3 Half Bridge	07-NOV-06
NA Control Type	170	07-NOV-06
	190	
NA1 motor type	None	07-NOV-06
NXE Arch. revision	no revision	29-JUL-14
NXT Arch. revision	no revision	16-JUL-10
Net lot overhead optimization for exposure sequence	No optimization	03-NOV-15
Nitrogen Purge Utility Control	Absent	07-NOV-06
Nitrogen purging of Reticle Stage	RS is not purged	07-NOV-06
Number of Active Elements	2	07-NOV-06
Number of Active Lens Elements	0	07-NOV-06
Number of Active Manipulator Elements	0	07-NOV-06
Number of Bi-directional Active Lens Elements	2	07-NOV-06
Number of EXLE elements	0	21-OCT-08
	1	
Number of Half Dome Mirrors	2	07-NOV-06
Number of Lens NEXZ Manipulators	6	07-NOV-06
Number of Lens Z Manipulators Using Camdisk	0	07-NOV-06
Number of Motion Controllers	5 Motion Controllers present	07-NOV-06
Number of RMCS clients	No clients	07-NOV-06
Number of Rxm	6	07-NOV-06
Number of Rym	6	07-NOV-06
Number of Semi-Active X-Y Lens Manipulators	6	07-NOV-06

Number of Z Lens Manipulators	6	07-NOV-06
Number of active mirror elements used in NXE POB	Zero active mirror elements	29-JUL-14
Number of bending points (mirrors).	Not applicable.	29-JUL-14
Number of manipulable ELLE axes	5	07-NOV-06
	6	
Number of pre-amps available per Z-manipulator	0	07-NOV-06
Number of supported fast Zernikes	ILIAS number of supported Zernikes 25	29-JUL-14
OADB Improved Dynamic Range	Enabled	21-OCT-08
OASIS	OASIS absent	29-JUL-14
OIU display hardware	OIU display is implemented by a Sun Workstation	29-JUL-14
Off-axis slit	Projection lens has an off-axis slit.	07-NOV-06
Online Lamp Peak	Disable Online Lamp Peak;	03-SEP-10
Option to apply the usage of HO marks in StageAlign	Use XPA marks in StageAlign.	16-JUL-10
Overlay Data Collection	Overlay Data Collection disabled.	16-JUL-10
Overlay Node	Level 0	07-NOV-06
Overlay Node for Boost Mode Lot's	Level 53	24-DEC-17
PCE Location	pce in APEX	16-JUL-10
PDGC correction subrecipe deletion	Enable deletion of ASML created PDGCCorr subrecipes	12-APR-21
PDOC correction subrecipe deletion	Enable deletion of ASML created PDOCCorr subrecipes	12-APR-21
PDOC quality indicator check	PDOC quality indicator functionality is absent	28-MAR-17
PED control mode	Absent	07-NOV-06
PEP High SLIP	PEP High SLIP is disabled	11-DEC-10
PEP Image Streaming	Present	07-NOV-06
PEP-ADC Intensity	Disable PEP-ADC Intensity;	03-SEP-10
POB Type	31	29-JUL-14
POB temperature sensors	No temperature sensor present	29-JUL-14
PSE Location	pse in PSER	16-JUL-10
PSE type	XY polarization	16-JUL-10
PSE-type of PSE located in ROE (Asymmetrical or Symmetrical)	Not Applicable	24-DEC-17
PUPICOM	Present	07-NOV-06
PUPICOM Architecture	Multi Spoke	07-NOV-06

PUPIL Measurement For Lithoguide	Present	07-NOV-06
PUPILIAS matching in terms of sigma measurement	Match ILIAS MK5 to MK4	
	No matching	16-JUL-10
PVP for disabling the laser burst interaction functionality	Enabled	29-JUL-14
Parameter indicates how long overlay data will be stored.	Short retention period.	16-JUL-10
Particle Extraction Mass Flow Meter	Absent	16-JUL-10
Patch strategy	Patchlevel	21-OCT-08
Pattern Matcher	Absent	16-JUL-10
Pattern Matcher Full Chip	Absent	16-JUL-10
Performance Enhancement Package	None	07-NOV-06
Physical location of OIU.	Not applicable.	29-JUL-14
Piezo Active Lens Mounts	Analog	07-NOV-06
	Digital MK-1	
Point-to-Point LS Machine Matching	Disabled	07-NOV-06
Polarization	Present	07-NOV-06
Polarization Shaping Element Retractor	PSER hardware installed in the machine	21-OCT-08
Polarized illumination amorph DOE.	Only unpolarized illumination.	21-OCT-08
Position Control Motion Control rack	MPCR	07-NOV-06
Position Control Power Rack Configuration	TYPE_4: Stages Power Rack upto F-spec	07-NOV-06
	TYPE_5: Stages Power Rack upto G-spec	
Position of Spot Sensor on Chuck 1	Spot Sensor Position on Chuck 1 layout 3	07-NOV-06
Position of Spot Sensor on Chuck 2	Spot Sensor Position on Chuck 2 layout 3	07-NOV-06
Possible triggers for disk cleaning	M-action can trigger disk cleaning	04-OCT-18
Power rack configuration	Phase_1/XTIII electronics (reduced safety settings)	16-JUL-10
Power supply type used for the wafer table BES heater.	Not applicable	16-JUL-10
Pressure update rate for fringelength correction	Pressure update rate 2 or 4 Hz	
	Pressure update rate 40 Hz	07-NOV-06
Process Dependent Gain Correction	Present	20-AUG-09
Projection GPA Configuration Version	Version 2	07-NOV-06
Provides improved TIS CPD when enabled.	Provides improved TIS CPD for diagnostics only	03-NOV-15
Proximity Matching	Present	07-NOV-06

Pupil TIS angular sensitivity calibration and correction	TIS Pupil Measurement will not be improved	21-OCT-08
Pupil forming optics	Zoom, axicon and DOE	16-JUL-10
Pupil measurements with ILIAS	Present	07-NOV-06
Pupil qualification method	Centre of gravity method	21-OCT-08
	Geometric centre method	
Purge Hoods configuration	Extremely Clean Dry Air only	07-NOV-06
REMA architecture	XTREMA	07-NOV-06
RS Object Field	Shifted 17x0	07-NOV-06
	Shifted 19x0	
RSC small NA correction.	RSC small NA correction is OFF.	29-JUL-14
Rapid prototyping using Python to control the machine.	Disable rapid prototyping.	16-JUL-10
ReMa mark	Mark1	
	Mark2	18-JUL-15
Readout location of Pneumatic Facility Unit sensors	CT sensor board (CTS)	07-NOV-06
Recipe Creator	Absent	07-NOV-06
Reduce RS preptime for ILIAS scans.	Use default ILIAS preptime	03-NOV-15
Reduce wafer-load-offset tolerance of centring unit to 25 um	Standard	11-DEC-10
Reduced capture range for TIS scans	Disable reduced range TIS scan scenarios	16-JUL-10
	Enable reduced range TIS scan scenarios	
Relative direction of ws to rs on the X axis	Same	07-NOV-06
Reorder Lot Service	Present	11-SEP-07
Report if a Recipe was modified by remote Host or Operator.	Do not report how Recipe was changed.	16-MAY-16
Reporting of K9/K10 coefficients from reticle alignment	RA_K9_K10_DATA_COLLECTION is Disabled	04-OCT-18
Reticle Align High Precision	Absent	07-NOV-06
	Present	
Reticle Balance Mass 1 amp.	450V20A: PAAC AT-pepD	07-NOV-06
	550V25A: PAAC XT rev3	
Reticle Balance Mass 2 amp.	450V20A: PAAC AT-pepD	07-NOV-06
	550V25A: PAAC XT rev3	
Reticle Carrier Location	Left	07-NOV-06
Reticle Carrier Tag Reader	Present	07-NOV-06

Reticle Handler Machine Architecture	Reticle Handler is designed to handle reticles in air.	16-JUL-10
Reticle Handler type	RH Mark IV	07-NOV-06
Reticle Heating Control	Reticle Heating Control is disabled	04-MAY-11
Reticle Heating Control acceptance test: zero layer reticle	RHC not supported	12-APR-21
Reticle Level Polarization Sensor	Present	17-NOV-06
Reticle Size	6 inch	07-NOV-06
Reticle Stage Chuck Type	TYPE_4: MGC_CLT, Glued LS, Magn. GC, ENC	15-FEB-12
	TYPE_6: Two part chuck	
Reticle Stage Lenscooler Box	Lenscooler Box with anti-aliasing Filter	07-NOV-06
Reticle Stage Long Stroke Config	TYPE_5:CoFe_18 motor,SIOB contr.,int. vacuum supply,magn. GC	16-JUL-10
	TYPE_6:CoFe_18+magn.cooling,SIOB,int. vacuum supply,magn. GC	
Reticle Stage Long Stroke Motor Type	Cobalt Ferro 18 teeth	07-NOV-06
Reticle Stage Long Stroke Y11 amp.	450V20A: PAAC AT-pepD	07-NOV-06
	550V25A: PAAC XT rev3	
Reticle Stage Long Stroke Y12 amp.	450V20A: PAAC AT-pepD	07-NOV-06
	550V25A: PAAC XT rev3	
Reticle Stage Long Stroke Y13 amp.	Don't care	16-JUL-10
Reticle Stage Long Stroke Y21 amp.	450V20A: PAAC AT-pepD	07-NOV-06
	550V25A: PAAC XT rev3	
Reticle Stage Long Stroke Y22 amp.	450V20A: PAAC AT-pepD	07-NOV-06
	550V25A: PAAC XT rev3	
Reticle Stage Long Stroke Y23 amp.	Don't care	16-JUL-10
Reticle Stage Measurement System on Scan	Heidenhain Encoders	07-NOV-06
Reticle Stage Short Stroke X amp.	PADC 100V/18A	07-NOV-06
	PADC 52V/6A	
Reticle Stage Short Stroke Y11 amp.	PADC 100V/18A	07-NOV-06
	PADC 130V/24A	
Reticle Stage Short Stroke Y12 amp.	PADC 100V/18A	07-NOV-06
	PADC 130V/24A	
Reticle Stage Short Stroke Y21 amp.	PADC 100V/18A	07-NOV-06
	PADC 130V/24A	

Reticle Stage Short Stroke Y22 amp.	PADC 100V/18A	07-NOV-06
	PADC 130V/24A	
Reticle Stage Short Stroke Z1 amp.	PADC 100V/18A	07-NOV-06
	PADC 52V/6A	
Reticle Stage Short Stroke Z2 amp.	PADC 100V/18A	07-NOV-06
	PADC 52V/6A	
Reticle Stage Short Stroke Z3 amp.	PADC 100V/18A	07-NOV-06
	PADC 52V/6A	
Reticle Stage Short Stroke Z4 amp.	Don't care	16-JUL-10
Reticle Stage purged mini environment	Present	07-NOV-06
Reticle Streaming 3	Reticle Streaming 3 Disabled	16-MAY-16
Reticle Temperature Sensor	RTS hardware is absent.	04-MAY-11
Reticle align capture	Always capture the reticle	16-JUL-10
Reticle alignment scenarios	XT reticle align scenarios	16-JUL-10
Reticle exchange type	Retex option: E	07-NOV-06
Reticle load protection for too wide/wrongly placed pellicle	Disabled	16-JUL-10
Reticle shape correction	Enabled	07-NOV-06
Reticle stage parking	Disabled	29-JUL-14
Reticle streaming	Disabled	21-OCT-08
Reticle streaming II	Disabled	16-JUL-10
Reticle streaming lite	Disabled	21-OCT-08
Robot Network Type	TYPE_1: Compensation filters are enabled	29-JUL-14
Robot position adjustment	DISABLED	19-MAR-19
SAMOS Stray Light Test For Lithoguide	Present	07-NOV-06
SASO robustness and fiber connectivity	Enable SASO robustness	20-JUL-12
SDM test on machines without SAXY elements	Disabled	11-DEC-10
SECS overlay corrections per exposure	Not allowed	04-OCT-18
SMASH Reuse Capture Information in Stage Alignment	Coarse capture scans are done on all stage alignment marks.	16-JUL-10
SPM Dual Speed Data Delay	Absent	29-JUL-14
SPM WS Optimized Sampling	Disable optimized phase capturing	29-JUL-14
SPM WS Optimized Sampling TOP4	Disable optimized phase capturing	29-JUL-14

SPM reference axis at measure side (XT ARA)	No reference axis at measure side available	16-JUL-10
SPM temp correction for lens axis	Disabled	21-OCT-08
Save throughput data to the disk	Disabled	25-APR-07
	Enabled	
Scaling of Lot Correction field effects	Scaling of Lot Correction functionality is absent	03-NOV-15
Scan Direction Matching	Disable Scan direction matching	29-JUL-14
Scanner Control Host hardware type VP item	This TWINSCAN has a SUN Fire 240 as SCH	03-NOV-15
	This TWINSCAN has a SUN Netra 240 as SCH	
Scanning Energy Sensor Calibration	Scanning Energy Sensor Calibration	07-NOV-06
Select Reticle Puffing Availability	Reticle Puff Not Available	03-NOV-15
Set PUPICOM use	N_A	16-JUL-10
Set UNICOM use	N_A	16-JUL-10
Set new TOPRC MPM model	Use New Mechanical Prediction Model (2) for TOP-RC	29-JUL-14
Settle time reduction to improve the throughput	Default settle times	16-JUL-10
Setup sensor board version	Setup SSD version LSDB	07-NOV-06
Shot Data Collection	Absent	07-NOV-06
Sigma Blade Exchanger	SBE absent	29-JUL-14
Single set of MCs for normal and Gridmapper expose scans.	mapping enabled;	29-JUL-14
Skip LS spots on TIS gratings for iVSA	Disabled	16-JUL-10
Smooth Field Uniformity	Absent	07-NOV-06
Specifies chuck1 config	Immersion mark 3	07-NOV-06
Specifies chuck1 layout relev. for Immersion	TYPE_2:t.b.d.	07-NOV-06
Specifies chuck1 version	Version 2	07-NOV-06
Specifies chuck2 config	Immersion mark 3	07-NOV-06
Specifies chuck2 layout relev. for Immersion	TYPE_2:t.b.d.	07-NOV-06
Specifies chuck2 version	Version 2	07-NOV-06
Specifies which mark types are supported	ASML marks and custom marks	
	ASML marks only	21-OCT-08
Spot Sensor Chuck 1	VLOC	07-NOV-06
Spot Sensor Chuck 2	VLOC	07-NOV-06
Spot Sensor Reticle Stage	Present	07-NOV-06

Spotsensor chuck 1 surface coating	SiO2	21-MAR-19
Spotsensor chuck 2 surface coating	Bilatal	16-JUL-10
	SiO2	
Stage Alignment Filter	Absent	07-NOV-06
Stage Alignment Phases	Coarse and Fine stage alignment	
	Fine stage alignment	16-JUL-10
Stage align just before FIWA	Disabled	16-JUL-10
Stages Sample Rate	5.0 kHz	07-NOV-06
Stages servo performance	Default servo performance	29-JUL-14
Stand-alone Workstation	False	07-NOV-06
Stressless wafer load for WS	Version 0	16-JUL-10
Striping correction ILIAS sensor	Disabled	06-NOV-10
	Enabled	
Swap bridge 1 type	No swap bridge available	29-JUL-14
Swap bridge 2 type	No swap bridge available	29-JUL-14
Switch INFORMPRO2 Data Package reporting	InformPro2 is unavailable	04-OCT-18
Symmetrical Reticle Alignment	Enabled	02-FEB-07
THFFC FDE model lens dependent	Disabled	21-OCT-08
	Enabled	
TIS Power switching	Disabled	16-JUL-10
TIS diffuser	TIS diffuser absent	21-OCT-08
	TIS diffuser present	
TIS overlay and TPT node	TIS Overlay and Throughput Performance Node 17	16-JUL-10
	TIS Overlay and Throughput Performance Node 19A	
TIS plate deformation correction	Enabled	21-FEB-08
TIS plate usage in reticle align	RA always measures TIS1 and TIS2	16-JUL-10
TIS plate usage in stage align	SA always measures TIS1 and TIS2	16-JUL-10
TIS trigger mechanism	Use internal trigger mechanism	16-JUL-10
TIS_ITOP	Disabled	16-JUL-10
	Enabled	
TOP HD	Present	07-NOV-06

Test Table	Absent	07-NOV-06
Test Table Z Axis	Worm Wheel	07-NOV-06
Test table architecture	Aerial XP	07-NOV-06
The cpu for 2DM software.	Absent	16-JUL-10
The exposure field size to be used during the TPT test	Narrow Field size	23-MAR-15
The version indicates who implements the PFNI dose sequence	Metrology implements the PFNI dose sequence	19-MAR-19
To enable large range leveling improved PDGC calibration.	Improved large range PDGC disabled	28-MAR-17
To enable the closing wafer refresh functionality	Disabled	06-NOV-10
To indicate which 2D clamping spec shall be used.	The 2D clamping spec is unknown.	28-MAR-17
To indicate which 2D exposure spec shall be used.	The 2D exposure spec is unknown.	28-MAR-17
To indicate which FQ spec shall be used	The fq spec is disabled	28-MAR-17
To indicate which SDM spec shall be used.	The SDM spec is unknown.	28-MAR-17
To indicate which data delay spec shall be used.	The data delay spec is unknown.	28-MAR-17
To indicate which distortion spec shall be used.	The overlay spec is unknown.	16-MAY-16
To indicate which final xy spec shall be used.	The final xy spec is unknown.	28-MAR-17
To indicate which fine SDM spec shall be used.	The fine SDM spec is unknown.	28-MAR-17
To indicate which focal spec shall be used.	The focal spec is unknown.	28-MAR-17
To indicate which overlay spec shall be used.	The overlay spec is unknown.	16-MAY-16
To indicate which repeatability spec shall be used.	The overlay spec is unknown.	16-MAY-16
To switch OFF D2x and D2y corrections for LoCoE and 860lens	D2x and D2y corrections for LOCO E and 860 lens are OFF	29-JUL-14
To switch ON usage of multiple BA-XY reticle types, namely V1 or V2	BA-XY reticle type is V1	23-MAR-15
Track Pre-warning signal (APR)	APR disabled	
	APR enabled	21-OCT-08
Turns on second waferstage host in atca rack	WS2 host is absent, and CSGR must not try to boot it	29-JUL-14
Twinscan GUI display location	Twinscan is displayed at the OIU display	29-JUL-14
Twinscan autostart	Twinscan autostart is enabled	29-JUL-14
Type of 1st general purpose amp	TAPA	16-JUL-10
Type of 5th general purpose amp	TAPA	16-JUL-10
Type of Air Gauge	TYPE_1: Initial version	20-AUG-09
Type of Clamp Flow Unit installed for Wafer Stage	Clamp Flow Unit version installed is irrelevant	12-APR-21
Type of E-pin tips installed for Wafer Stage	Stiff E-pin tips	12-APR-21

Type of LS capture	Stepping	29-JUL-14
Type of MDRC used.	Not applicable.	29-JUL-14
Type of NEXZ actuator	NEXZ with 885nm range (NO3)	06-NOV-10
Type of PARIS sensor on chuck 1	No PARIS sensor on chuck 1	29-JUL-14
Type of PARIS sensor on chuck 2	No PARIS sensor on chuck 2	29-JUL-14
Type of e-pins calibration for Wafer Stage	1DOF (z only)	
	Not applicable	11-DEC-10
Type of immersion hood for immersion	Actuator Fixed Height	07-NOV-06
Type of inline cleaning cabinet	ILCC absent	16-JUL-10
Type of level sensor gratings.	30um pitch grating for 16um LS Period	03-NOV-15
Type of measurement carried out as SFPM measurement	The SFPM measurement is disabled	16-JUL-10
Type of projection multiplexer board	MUX type LAMB	07-NOV-06
Type of wafertable on chuck 1 for immersion machine	SiSiC version 4	20-AUG-09
	SiSiC version 5	
Type of wafertable on chuck 2 for immersion machine	SiSiC version 4	20-AUG-09
	SiSiC version 5	
UNICOM	Present	07-NOV-06
UNICOM Architecture	58 Motors	07-NOV-06
UPW Unit	Type A or type B UPW Unit installed	21-OCT-08
	Type C UPW Unit installed	
UV Shutter version	UV Shutter version 1	07-NOV-06
Ultra Pure Water Cabinet (UPWC) version	NO UPWC installed	29-JUL-14
Ultra Pure Water flow controller (WICC)	Entegris NT Flow Controller	20-OCT-07
Unicom move check	Unicom move check enabled	07-AUG-17
Uniformity Improvement Package	Present	07-NOV-06
Universal Prealignment	Disabled	07-NOV-06
	Enabled	
Unload Robot Wrist Assy Type	WH UR Wrist Long Tension Rod	16-JUL-10
Unprepare fully preprocessed lot for M-actions	Disabled	12-APR-21
Usage of Energy Sensor data by TIS	Enabled	07-NOV-06
Usage of wavelength data by TIS	Enabled	07-NOV-06

Use Ryx or Ryz for the x Abbe correction	Not applicable	11-DEC-10
	Use Ryx for the x Abbe correction	
Use Sigma Calibration	apply Sigma Calibration	21-OCT-08
Use Sigma WIP Preserving Offsets	no Sigma WIP Preserving Offsets	21-OCT-08
Use TIS1-TIS2 Reticle Alignment scenario for K-spec	TIS1-TIS2 Reticle Alignment scenario for K-spec is ENABLED	29-JUL-14
Use a servo setting set	Default servo setting	29-JUL-14
Use improved setpoint calculations for shifted images	Improved setpoint calculations are ENABLED	29-JUL-14
Use the old at4.0.3 SPE sequence (ASF)	Do not overrule the SPE sequence	16-JUL-10
Use validity ranges around UIP data when Enabled.	Use exact matching for UIP data	21-OCT-08
Version of RS/WS IO library	Version 1	07-NOV-06
	Version 2	
Version of the Air Control Cabinet (ACC)	ACC MK 1 to 4	16-JUL-10
WES 2000M hardware presence	Absent	16-JUL-10
	Present	
WH Dock spring leaf cam typ	Hard	
	Soft	29-JUL-14
WH Robot Power Amplifier	CPM 20	07-NOV-06
WH temperature conditioning type	Slow performance type used for XTIII and below.	16-JUL-10
WS 14db controller.	WS 14db controller DISABLED.	29-JUL-14
WS Balance Mass	Stainless Steel	07-NOV-06
WS Immersion Hood Only Testrig	Absent	07-NOV-06
WS Immersion throughput package	Tiger mode chuck swap closing disc exchange	16-JUL-10
WS Immersion wafer table thermal control package	Single BES heater and cold-end wafer table heater	16-JUL-10
	Six segmented BES heater and cold-end wafer table heater	
WS Wafer Align Scans	Default	28-MAR-17
WS Zeroing using Absolute Phase Capturing	Off	29-JUL-14
WS improved step/scan behaviour.	Standard step/scan behaviour	29-JUL-14
WS prediction of wafer exchange timing	Default	25-MAY-18
WS servo error is fed to RS for better combined performance	disabled	07-AUG-17
WVAC Unit	Type A WVAC Unit installed	21-OCT-08
	Type B WVAC Unit installed	

Wafer Carrier Location	Left	07-NOV-06
Wafer Handler Pre-aligner Type	Pre-aligner with air-bearing table	12-APR-21
Wafer Handler Productivity	Wafer Handler Productivity Level 1	07-NOV-06
Wafer Handler wrt BF Shifted in Z	Not Shifted	07-NOV-06
Wafer Handling Docking Plate	WH Docking Plate Extra Low Height	16-JUL-10
Wafer Handling Drying Unit	WH Drying Unit Absent	16-JUL-10
Wafer Handling Load Robot Type	Scara Arm, 40 mm Z stroke	07-NOV-06
Wafer Handling Pneumatics	Standard	07-NOV-06
Wafer Handling Store Unit Type	WH Store Unit 3 Slotted	16-JUL-10
Wafer Handling TSU	WH TSU Heater Absent	16-JUL-10
Wafer Handling Track Input	WH Wafer Track Input Via PU	16-JUL-10
Wafer Handling Unload Robot Type	Scara Arm, 40 mm Z stroke	07-NOV-06
Wafer Id Reader	Absent	07-NOV-06
Wafer Mark Sensor	Absent	
	Present	07-NOV-06
Wafer Size	300mm	07-NOV-06
Wafer Stage Balance Mass 11 amp.	Don't care	07-NOV-06
Wafer Stage Balance Mass 12 amp.	Don't care	07-NOV-06
Wafer Stage Balance Mass 21 amp.	Don't care	07-NOV-06
Wafer Stage Balance Mass 22 amp.	Don't care	07-NOV-06
Wafer Stage Coarse Wafer Align Improvement	None	07-AUG-17
Wafer Stage Configuration	Wafer Stage type 3 configuration	07-NOV-06
	Wafer Stage type 4 configuration	
Wafer Stage Dedicated Hardware Configuration	None	06-NOV-10
Wafer Stage Expose Scan Strategy	Default	28-MAR-17
Wafer Stage Fast Stiff X Move Electronics	Present	07-NOV-06
Wafer Stage Long Stroke E CS amp.	450V20A: PAAC AT-pepD	07-NOV-06
	550V25A: PAAC XT rev3	
Wafer Stage Long Stroke E X amp.	450V20A: PAAC AT-pepD	07-NOV-06
	550V25A: PAAC XT rev3	
Wafer Stage Long Stroke E Y1 amp.	450V20A: PAAC AT-pepD	07-NOV-06

	550V25A: PAAC XT rev3	
Wafer Stage Long Stroke E Y2 amp.	450V20A: PAAC AT-pepD	07-NOV-06
	550V25A: PAAC XT rev3	
Wafer Stage Long Stroke M CS amp.	450V20A: PAAC AT-pepD	07-NOV-06
	550V25A: PAAC XT rev3	
Wafer Stage Long Stroke M X amp.	450V20A: PAAC AT-pepD	07-NOV-06
	550V25A: PAAC XT rev3	
Wafer Stage Long Stroke M Y1 amp.	450V20A: PAAC AT-pepD	07-NOV-06
	550V25A: PAAC XT rev3	
Wafer Stage Long Stroke M Y2 amp.	450V20A: PAAC AT-pepD	07-NOV-06
	550V25A: PAAC XT rev3	
Wafer Stage Measurement System	Agilent interferometers	16-JUL-10
Wafer Stage Mirror Block Down Electronics	Absent	07-NOV-06
Wafer Stage Overlay Diagnostics	Disabled	16-MAY-16
Wafer Stage Short Stroke 1 XY1 amp.	PADC 100V/18A	07-NOV-06
	PADC 130V/24A	
Wafer Stage Short Stroke 1 XY2 amp.	PADC 100V/18A	07-NOV-06
	PADC 130V/24A	
Wafer Stage Short Stroke 1 XY3 amp.	PADC 100V/18A	07-NOV-06
	PADC 130V/24A	
Wafer Stage Short Stroke 1 Z1 amp.	PADC 100V/18A	07-NOV-06
	PADC 52V/6A	
Wafer Stage Short Stroke 1 Z2 amp.	PADC 100V/18A	07-NOV-06
	PADC 52V/6A	
Wafer Stage Short Stroke 1 Z3 amp.	PADC 100V/18A	07-NOV-06
	PADC 52V/6A	
Wafer Stage Short Stroke 2 XY1 amp.	PADC 100V/18A	07-NOV-06
	PADC 130V/24A	
Wafer Stage Short Stroke 2 XY2 amp.	PADC 100V/18A	07-NOV-06
	PADC 130V/24A	
Wafer Stage Short Stroke 2 XY3 amp.	PADC 100V/18A	07-NOV-06

	PADC 130V/24A	
Wafer Stage Short Stroke 2 Z1 amp.	PADC 100V/18A	07-NOV-06
	PADC 52V/6A	
Wafer Stage Short Stroke 2 Z2 amp.	PADC 100V/18A	07-NOV-06
	PADC 52V/6A	
Wafer Stage Short Stroke 2 Z3 amp.	PADC 100V/18A	07-NOV-06
	PADC 52V/6A	
Wafer Stage Type	Dual Chuck	07-NOV-06
Wafer Switch	Absent	07-NOV-06
Wafer Track	Present	22-JAN-07
Wafer stage technology	Wafer stage H-drive	16-JUL-10
Wafer type used in the machine	300 mm - SEMI Notch	16-JUL-10
Wafer z-map type.	Type 1: Pre-calculated setpoints from GLC	29-JUL-14
Wafer-Handler Air-Extraction presence	WH Air-Extraction hardware is absent	03-NOV-15
Wafers per Carrier	25	07-NOV-06
Warped wafer shape support	Disabled	19-MAR-19
Wavelength Adjustable	Adjustable	07-NOV-06
Weighing of 2-Sided X-interferometers	Variable interferometer weight factors	16-MAY-16
Wet Chuck Ex. while stay hovering (Chuck1=Exp,Chuck2=Mea)	Not Applicable	16-JUL-10
Wet Chuck Ex. while stay hovering (Chuck1=Mea,Chuck2=Exp)	Not Applicable	16-JUL-10
Wet Imaging Control Cabinet	Type B	07-NOV-06
	Type C or Type D	
Wet Imaging Control Rack	WICR-i4 or WICR-i5	06-NOV-11
Wet Vacuum unit version in EIM	No WVAC EIM unit installed	29-JUL-14
Wide Pellicle Detection	Absent	16-JUL-10
Wide Pellicle Detection Type	DISABLED	29-JUL-14
XML Lot Report Content Level	Basic	16-JUL-10
XML output for LITHOGUIDE	Disabled	21-OCT-08
XT Architecture Revision	Rev2	07-NOV-06
	Rev3	
XT REMA MPAC board type	MPAC type 1	16-JUL-10

XT19x0 throughput performance enhancement package.	Not applicable	29-JUL-14
	Standard performance settings	
Z-capture on low reflectivity wafers	Z-capture on low reflectivity wafers is disabled.	11-DEC-10
ZERO Fiducial	ILIAS MK3	07-NOV-06
	ILIAS MK4	
Zeroing type for Encoders Measurement System	Using reference marks on the encoder scales	07-NOV-06
Zoom Axicon Architecture	ZZA	07-NOV-06
Zoom Axicon Type	170	07-NOV-06
	190	
board configuration	OADB	07-NOV-06
enables ihopc per image per chuck	disables ihopc per image per chuck	03-NOV-15
extended docking interface at Prealigner	ECC_OMM	07-NOV-06
mbds control	Present	07-NOV-06
purging configuration	purging CONFIG 3	23-MAY-07
	purging CONFIG 8	
routing for ASML test purposes	Disabled	21-OCT-08
switch for 3DOF / 6DOF HDM	HDM_TYPE_6DOF	16-JUL-10
wildcard matching to reuse reticle heating TOPRC records	Reticle heating control calibration record reuse is disabled	03-NOV-15